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TRANSMITTAL FORM (to be used for all correspondence after initial filing)	Application Number	10/729,169
	Filing Date	December 4, 2003
	First Named Inventor	Robert David ALLEN et al.
	Art Unit	1713
	Examiner Name	Unassigned
Mail Stop	Attorney Docket Number	ARC920030103US1

ENCLOSURES (Check all that apply)

<input checked="" type="checkbox"/> No fee due <input type="checkbox"/> Fee Transmittal <input type="checkbox"/> Fee(s) due <input type="checkbox"/> Fee Transmittal <input type="checkbox"/> Check for \$* <input checked="" type="checkbox"/> Charge any underpayment or credit any overpayment to Deposit Account No. 09-0441 <input checked="" type="checkbox"/> Return postcard <input type="checkbox"/> Amendment/Reply <input type="checkbox"/> After Final <input type="checkbox"/> Affidavits/declaration(s) <input type="checkbox"/> Extension of Time Request <input type="checkbox"/> Express Abandonment Request <input checked="" type="checkbox"/> Information Disclosure Statement & Form(s) PTO-1449 <input checked="" type="checkbox"/> Copy(ies) of cited reference(s) <input type="checkbox"/> Certified Copy of Priority Document(s) <input type="checkbox"/> Response to Missing Parts / Incomplete Application <input type="checkbox"/> Response to Missing Parts under 37 CFR 1.52 or 1.53	<input type="checkbox"/> Drawing(s) <input type="checkbox"/> Licensing-related Papers <input type="checkbox"/> Petition <input type="checkbox"/> Petition to Convert to a Provisional Application <input type="checkbox"/> Power of Attorney, Revocation, Change of Correspondence Address <input type="checkbox"/> Terminal Disclaimer <input type="checkbox"/> Request for Refund <input type="checkbox"/> CD, Number of CD(s):	<input type="checkbox"/> After Allowance Communication to a Technology Center (TC) <input type="checkbox"/> Appeal Communication to Board of Appeals and Interferences <input type="checkbox"/> Appeal Communication to TC (Appeal Notice, Brief, Reply Brief) <input type="checkbox"/> Proprietary Information <input type="checkbox"/> Status Letter <input type="checkbox"/> Other Enclosure(s) (please identify below):
Remarks:		

SIGNATURE OF APPLICANT, ATTORNEY, OR AGENT

Firm or Individual Name (print/type)	Dianne E. Reed, Registration No. 31,292 Reed & Eberle LLP	Telephone	(650) 330-0900
Signature		Date	3/22/04

CERTIFICATE OF TRANSMISSION/MAILING

I hereby certify that this correspondence is being deposited with the United States Postal Service with sufficient postage as first class mail in an envelope addressed to: Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450 on the date shown below.			
Name (print/type)	Will Sayo		
Signature		Date	3.22.04



Atty Dkt No. ARC920030103US1
R&E No. 5075-0041
PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In Re Application of:

Robert David ALLEN et al.

Confirmation No.: 8945

Serial No.: 10/729,169

Group Art Unit: 1713

Filing Date: December 4, 2003

Examiner: Unassigned

Title: LOW ACTIVATION ENERGY PHOTORESISTS

INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

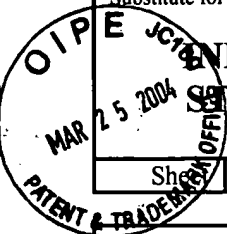
Sir:

This is an Information Disclosure Statement submitted for the Examiner's consideration. Applicants respectfully request that the Examiner review and make of record the references identified below.

A PTO-1449 form listing the references accompanies this paper. Applicants would appreciate the Examiner's initialing and returning the form to indicate that the references have been reviewed and made of record. The references are as follows:

U.S. PATENT DOCUMENT		
Document No.	Issue Date or Publication Date	Name of Patentee or Applicant
5,391,587	2/21/95	Wu
5,665,527	9/9/97	Allen et al.
5,919,597	7/6/99	Sinta et al.
6,037,097	3/14/00	Bucchignano et al.
6,043,003	3/28/00	Bucchignano et al.
6,265,135	7/24/01	Kodama et al.
Serial No. 10/716,785	Filed 11/19/03	Angelopoulos et al.
Serial No. 10/729,452	Filed 12/4/03	Robert David Allen et al.

FOREIGN PATENT DOCUMENTS		
Document No.	Publication Date	Country
WO 01/86352	11/15/01	PCT
WO 02/079287	10/10/02	PCT
WO 03/040827	5/15/03	PCT



Substitute for form 1449A/PTO

Complete if Known

**INFORMATION DISCLOSURE
STATEMENT BY APPLICANT**

(use as many sheets as necessary)

Application Number	10/729,169
Filing Date	December 4, 2003
First Named Inventor	Robert David ALLEN et al.
Art Unit	1713
Examiner Name	Unassigned
Attorney Docket Number	ARC920030103US1

Sheet 1 of 1

U.S. PATENT DOCUMENTS

Examiner Initials*	Cite No.	Document No.	Issue Date or Publication Date	Name of Patentee or Applicant of Cited Document	Class	Subclass	Filing Date if Appropriate
	AA	5,391,587	2/21/95	Wu			
	AB	5,665,527	9/9/97	Allen et al.			
	AC	5,919,597	7/6/99	Sinta et al.			
	AD	6,037,097	3/14/00	Bucchignano et al.			
	AE	6,043,003	3/28/00	Bucchignano et al.			
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	AG	Serial No. 10/716,785	Filed 11/19/03	Angelopoulos et al.			
	AH	Serial No. 10/729,452	Filed 12/4/03	Robert David Allen et al.			

FOREIGN PATENT DOCUMENTS

Examiner Initials*	Cite No.	Foreign Patent Document No.	Publication Date	Country	Class	Subclass	T
	AI	WO 01/86352	11/15/01	PCT			
	AJ	WO 02/079287	10/10/02	PCT			
	AK	WO 03/040827	5/15/03	PCT			

OTHER DOCUMENTS — NONPATENT LITERATURE DOCUMENTS

Examiner Initials*	Cite No.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), Title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T
	AL	BAE et al. (2003), "Rejuvenation of 248 nm Resist Backbones for 157 nm Lithography," <i>Journal of Photopolymer Science and Technology</i> 14(4):613-620.	
	AM	HINSBERG et al. (2000), "Effect of Resist Components on Image Spreading During Postexposure Bake of Chemically Amplified Resists," <i>Advances in Resist Technology and Processing XVII, Proceedings of SPIE</i> 3999:148-160.	
	AN	HINSBERG et al. (2003), "Extendibility of Chemically Amplified Resists: Another Brick Wall?," <i>Advances in Resist Technology and Processing XX, Proceedings of SPIE</i> 5039:1-14.	
	AO	HOULE et al. (2000), "Determination of Coupled Acid Catalysis-Diffusion Processes in a Positive-Tone Chemically Amplified Photoresist," <i>J. Vac. Sci. Technol. B</i> 18(4):1874-1885.	
	AP	ITO et al. (2001), "Polymer Design for 157 nm Chemically Amplified Resists," <i>Advances In Resist Technology And Processing XVIII, Proceedings Of SPIE</i> 4345:273-284.	
	AQ	KUNZ et al. (2001), "Experimental VUV Absorbance Study of Fluorine-Functionalized Polystyrenes," <i>Advances in Resist Technology and Processing XVIII, Proceedings of SPIE</i> 4345:285-295.	

Examiner Signature		Date Considered	
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*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

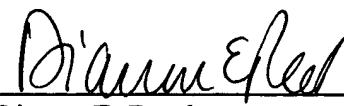
NONPATENT DOCUMENTS
BAE et al. (2003), "Rejuvenation of 248 nm Resist Backbones for 157 nm Lithography," <i>Journal of Photopolymer Science and Technology</i> <u>14</u> (4):613-620.
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KUNZ et al. (2001), "Experimental VUV Absorbance Study of Fluorine-Functionalized Polystyrenes," <i>Advances in Resist Technology and Processing XVIII, Proceedings of SPIE</i> <u>4345</u> :285-295.

As the subject application was filed after June 30, 2003, copies of the U.S. patents disclosed in this Information Disclosure Statement are not required and, therefore, are not included.

This Information Disclosure Statement is not intended as a representation that a search has been made, that additional information material to the examination of this application does not exist, or that any of the above references constitutes prior art to the present application within the meaning of 35 USC § 102.

As applicants have not yet received a first Action on the merits, no fee is required for filing this Information Disclosure Statement. If, however, the PTO finds that for some reason a fee is found to be necessary, our Deposit Account No. 18-0580 may be charged therefor.

Respectfully submitted,

By: 
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Registration No. 31,292

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